

# Kenneth Gonsalves

## List of Publications by Year in descending order

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papers

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citations

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g-index

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docs citations

57  
times ranked

558  
citing authors

#	ARTICLE	IF	CITATIONS
1	Organoiodine Functionality Bearing Resists for Electron-Beam and Helium Ion Beam Lithography: Complex and Sub-16 nm Patterning. ACS Applied Electronic Materials, 2021, 3, 1996-2004.	4.3	16
2	Resists for Helium Ion Beam Lithography: Recent Advances. ACS Applied Electronic Materials, 2020, 2, 3805-3817.	4.3	16
3	Functionalized Ag Nanoparticles Embedded in Polymer Resists for High-Resolution Lithography. ACS Applied Nano Materials, 2020, 3, 8651-8661.	5.0	7
4	Development of Nickel-Based Negative Tone Metal Oxide Cluster Resists for Sub-10 nm Electron Beam and Helium Ion Beam Lithography. ACS Applied Materials & Interfaces, 2020, 12, 19616-19624.	8.0	30
5	Organotin in Nonchemically Amplified Polymeric Hybrid Resist Imparts Better Resolution with Sensitivity for Next-Generation Lithography. ACS Applied Polymer Materials, 2020, 2, 1790-1799.	4.4	21
6	Mechanistic insights of Sn-based non-chemically-amplified resists under EUV irradiation. Applied Surface Science, 2020, 533, 146553.	6.1	10
7	Enhanced mechanical properties of the high-resolution EUVL patterns of hybrid photoresists containing hexafluoroantimonate. Microelectronic Engineering, 2018, 194, 100-108.	2.4	4
8	EUV photofragmentation study of hybrid nonchemically amplified resists containing antimony as an absorption enhancer. RSC Advances, 2018, 8, 10930-10938.	3.6	24
9	Ferrocene Bearing Non-ionic Poly-aryl Tosylates: Synthesis, Characterization and Electron Beam Lithography Applications. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2018, 31, 669-678.	0.3	2
10	Polarization Dependence in the Carbon K-Edge Photofragmentation of MAPDST Photoresist: An Experimental and Theoretical Study. Journal of Physical Chemistry C, 2018, 122, 28619-28628.	3.1	2
11	EUV photofragmentation and oxidation of a polyarylene sulfonium resist: XPS and NEXAFS study. Journal of Photochemistry and Photobiology A: Chemistry, 2018, 364, 373-381.	3.9	12
12	A photoacid generator integrated terpolymer for electron beam lithography applications: sensitive resist with pattern transfer potential. Materials Chemistry Frontiers, 2017, 1, 1895-1899.	5.9	11
13	Polyarylenesulfonium Salt as a Novel and Versatile Nonchemically Amplified Negative Tone Photoresist for High-Resolution Extreme Ultraviolet Lithography Applications. ACS Applied Materials & Interfaces, 2017, 9, 17-21.	8.0	21
14	Heavy metal incorporated helium ion active hybrid non-chemically amplified resists: Nano-patterning with low line edge roughness. AIP Advances, 2017, 7, 085314.	1.3	12
15	Organic-inorganic hybrid photoresists containing hexafluoroantimonate: design, synthesis and high resolution EUV lithography studies. Materials Chemistry Frontiers, 2017, 1, 2613-2619.	5.9	13
16	Design, development, EUVL applications and nano mechanical properties of a new HfO <sub>2</sub> based hybrid non-chemically amplified resist. RSC Advances, 2016, 6, 67143-67149.	3.6	28
17	Design and development of low activation energy based nonchemically amplified resists (n-CARs) for next generation EUV lithography. Microelectronic Engineering, 2016, 164, 115-122.	2.4	7
18	Recent advances in non-chemically amplified photoresists for next generation IC technology. RSC Advances, 2016, 6, 74462-74481.	3.6	32

#	ARTICLE	IF	CITATIONS
19	Patterning highly ordered arrays of complex nanofeatures through EUV directed polarity switching of non chemically amplified photoresist. Scientific Reports, 2016, 6, 22664.	3.3	9
20	New Polyoxometalates Containing Hybrid Polymers and Their Potential for Nano-Patterning. Chemistry - A European Journal, 2015, 21, 2250-2258.	3.3	32
21	Selective Fragmentation of Radiation-Sensitive Novel Polymeric Resist Materials by Inner-Shell Irradiation. ACS Applied Materials & Interfaces, 2015, 7, 16348-16356.	8.0	18
22	Performance evaluation of nonchemically amplified negative tone photoresists for e-beam and EUV lithography. Journal of Micro/ Nanolithography, MEMS, and MOEMS, 2014, 13, 043002.	0.9	22
23	Towards novel non-chemically amplified (n-CARS) negative resists for electron beam lithography applications. Journal of Materials Chemistry C, 2014, 2, 2118.	5.5	21
24	Radiation-Sensitive Novel Polymeric Resist Materials: Iterative Synthesis and Their EUV Fragmentation Studies. ACS Applied Materials & Interfaces, 2014, 6, 4223-4232.	8.0	44
25	Novel chemically amplified resists incorporating anionic photoacid generator functional groups for sub-50-nm half-pitch lithography. Journal of Materials Chemistry, 2009, 19, 2797.	6.7	29
26	The effect of direct PAG incorporation into the polymer main chain on reactive ion etch resistance of 193nm and EUV chemically amplified resists. Microelectronic Engineering, 2008, 85, 963-965.	2.4	8
27	Incorporation of ionic photoacid generator (PAG) and base quencher into the resist polymer main chain for sub-50 nm resolution patterning. Journal of Materials Chemistry, 2008, 18, 2704.	6.7	16
28	Fullerene Grafted Photoacid Generator (PAG) Bound Polymer Resists. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2008, 21, 747-751.	0.3	3
29	Novel anionic photoacid generators (PAGs) and corresponding PAG bound polymers for sub-50 nm EUV lithography. Journal of Materials Chemistry, 2007, 17, 1699.	6.7	40
30	Novel Anionic Photoacid Generators (PAGs) and Corresponding PAG Bound Polymers. Macromolecular Rapid Communications, 2006, 27, 1590-1595.	3.9	20
31	Novel polymeric anionic photoacid generators (PAGs) and corresponding polymers for 193 nm lithography. Journal of Materials Chemistry, 2006, 16, 3701.	6.7	44
32	Micro/nanomachining of Polymer Surface for Promoting Osteoblast Cell Adhesion. Biomedical Microdevices, 2003, 5, 101-108.	2.8	25
33	Micropatterns of a Cell-Adhesive Peptide on an Amphiphilic Comb Polymer Film. Langmuir, 2002, 18, 2975-2979.	3.5	53
34	New Photoresists with Photoacid Generator in the Backbone. Materials Research Society Symposia Proceedings, 2001, 705, 231.	0.1	0
35	A Versatile Approach for Biomaterial Patterning: Masked Ion Beam Lithography. Materials Research Society Symposia Proceedings, 2001, 705, 461.	0.1	2
36	Development of Nanostructures for Drug Delivery Applications. , 0, , 139-206.		1

#	ARTICLE	IF	CITATIONS
37	Nanotechnology and Drug Delivery. , 0, , 93-113.		4
38	Cell Behavior Toward Nanostructured Surfaces. , 0, , 261-295.		9
39	Nanofabrication Techniques. , 0, , 1-24.		0
40	Cellular Behavior on Basement Membrane Inspired Topographically Patterned Synthetic Matrices. , 0, , 297-319.		2
41	Focal Adhesions: Self-Assembling Nanoscale Mechanochemical Machines that Control Cell Function. , 0, , 321-335.		0
42	Controlling Cell Behavior via DNA and RNA Transfections. , 0, , 337-356.		0
43	Multiscale Coculture Models for Orthopedic Interface Tissue Engineering. , 0, , 357-373.		4
44	Nanostructures for Tissue Engineering/Regenerative Medicine. , 0, , 375-407.		5
45	Nanostructures for Cancer Diagnostics and Therapy. , 0, , 409-437.		2
46	Nanoscale Iron Compounds Related to Neurodegenerative Disorders. , 0, , 461-490.		1
47	Application of Nanotechnology into Life Science: Benefit or Risk. , 0, , 491-501.		0
48	Micro/Nanomachining and Fabrication of Materials for Biomedical Applications. , 0, , 25-47.		2
49	Novel Nanostructures as Molecular Nanomotors. , 0, , 49-60.		0
50	Bioconjugation of Soft Nanomaterials. , 0, , 61-91.		0
51	Polymeric Nanoparticles and Nanopore Membranes for Controlled Drug and Gene Delivery. , 0, , 115-137.		5
52	Bioconjugated Nanoparticles for Ultrasensitive Detection of Molecular Biomarkers and Infectious Agents. , 0, , 207-222.		1
53	ECM Interactions with Cells from the Macro- to Nanoscale. , 0, , 223-260.		4